

SUBSTRATE PROCESSING APPARATUS, SUBSTRATE PROCESSING METHOD,
AND STORAGE MEDIUM

ABSTRACT

5 A substrate processing apparatus includes a processing
tank, a lid body, a chemical liquid supply unit, a
pressurizing unit, and a controller. The processing tank has
an opening in an upper portion thereof, and immerses and
processes a substrate in a chemical liquid. The lid body is
10 configured to be capable of sealing the opening of the
processing tank. The chemical liquid supply unit supplies the
chemical liquid to the processing tank. The pressurizing unit
pressurizes the chemical liquid on an upstream side of the
chemical liquid supply unit. The controller controls each
15 unit. The controller immerses the substrate in the chemical
liquid retained in the processing tank, seals the opening of
the processing tank by the lid body, and supplies the chemical
liquid pressurized by the pressurizing unit to the processing
tank from the chemical liquid supply unit to pressurize the
20 chemical liquid retained in the processing tank.

Figure 5